

ELECTROETCHING PROCESS AND SYSTEM

ABSTRACT OF THE DISCLOSURE

5 [0036] A system for optionally depositing or etching a layer of a wafer includes mask plate opposed to the wafer with the mask plate having a plurality of openings that transport a solution to the wafer. An electrode assembly has a first electrode member and a second electrode member having channels that operatively interface a peripheral and center part of the wafer. The channels
10 transport the solution to the mask.